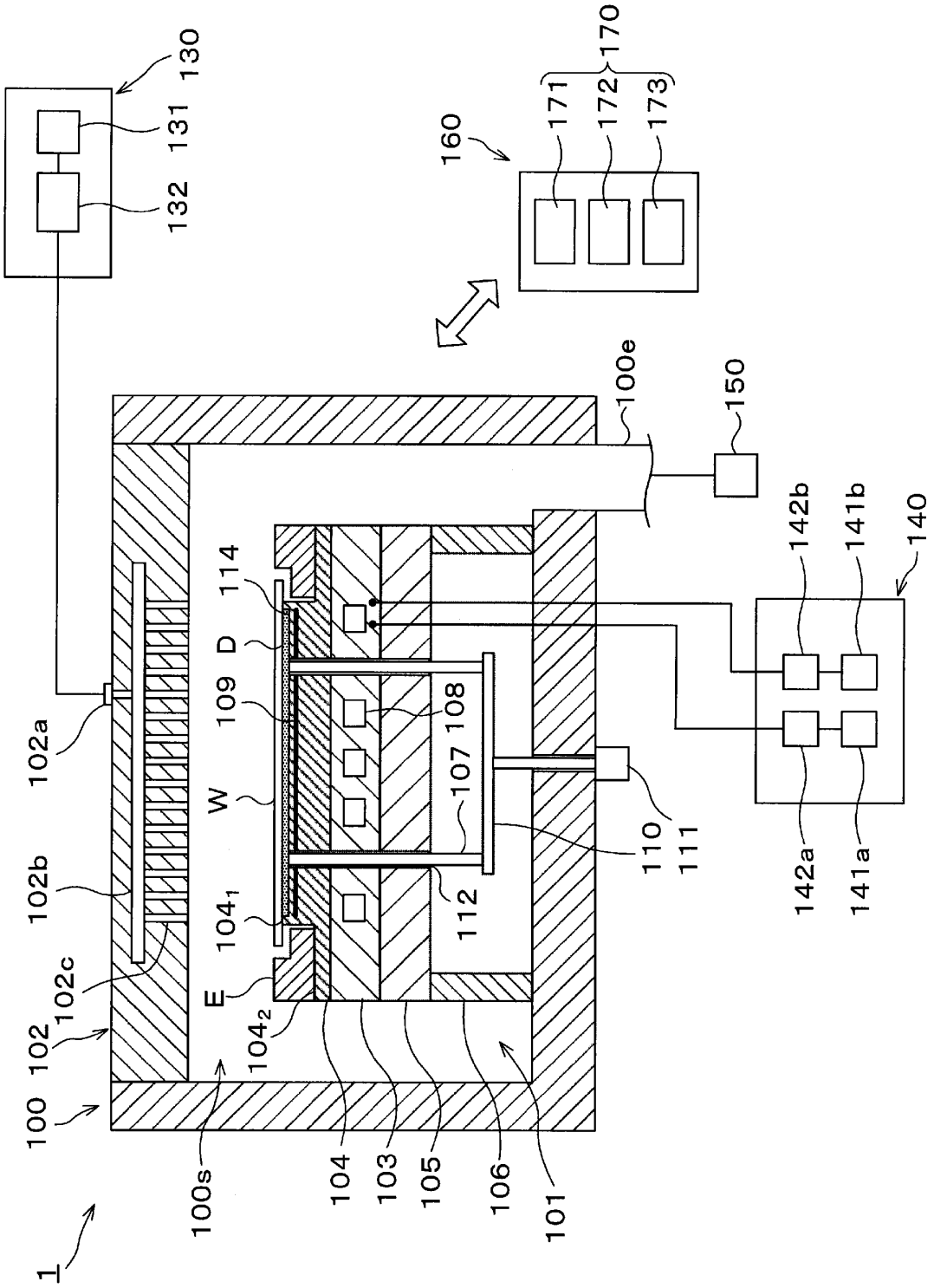
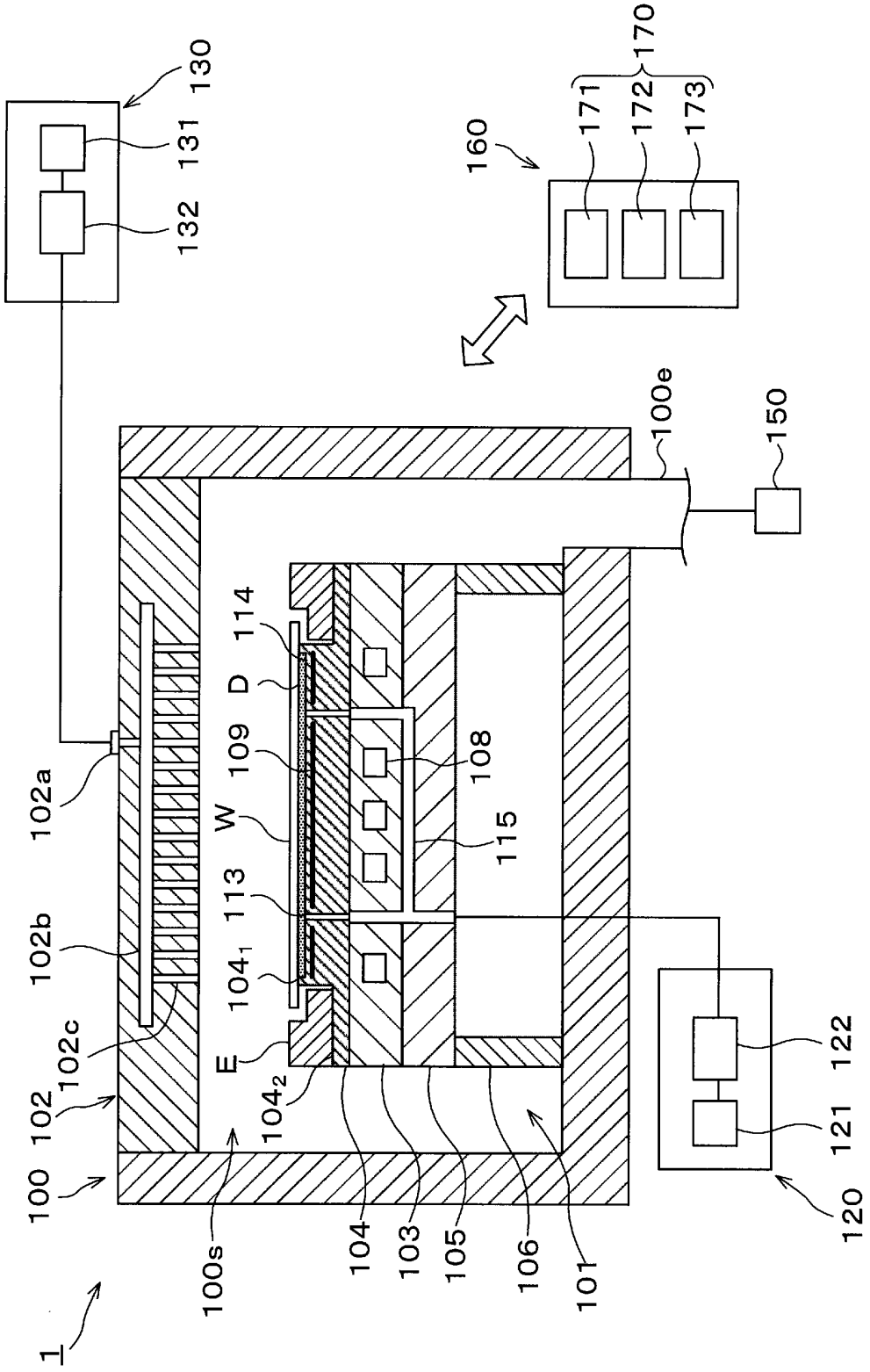
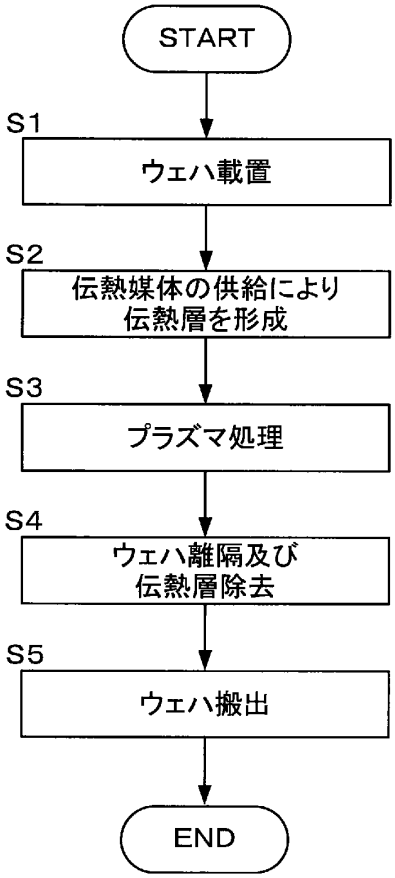
[図1]


130
131
132
160
170
171
172
173
100e
150
140
142b
141b
114
D
109
108
107
W
102a
102b
102c
102
100
104_1
E
104_2
112
110
111
142a
141a
100s
104
103
105
106
101
1

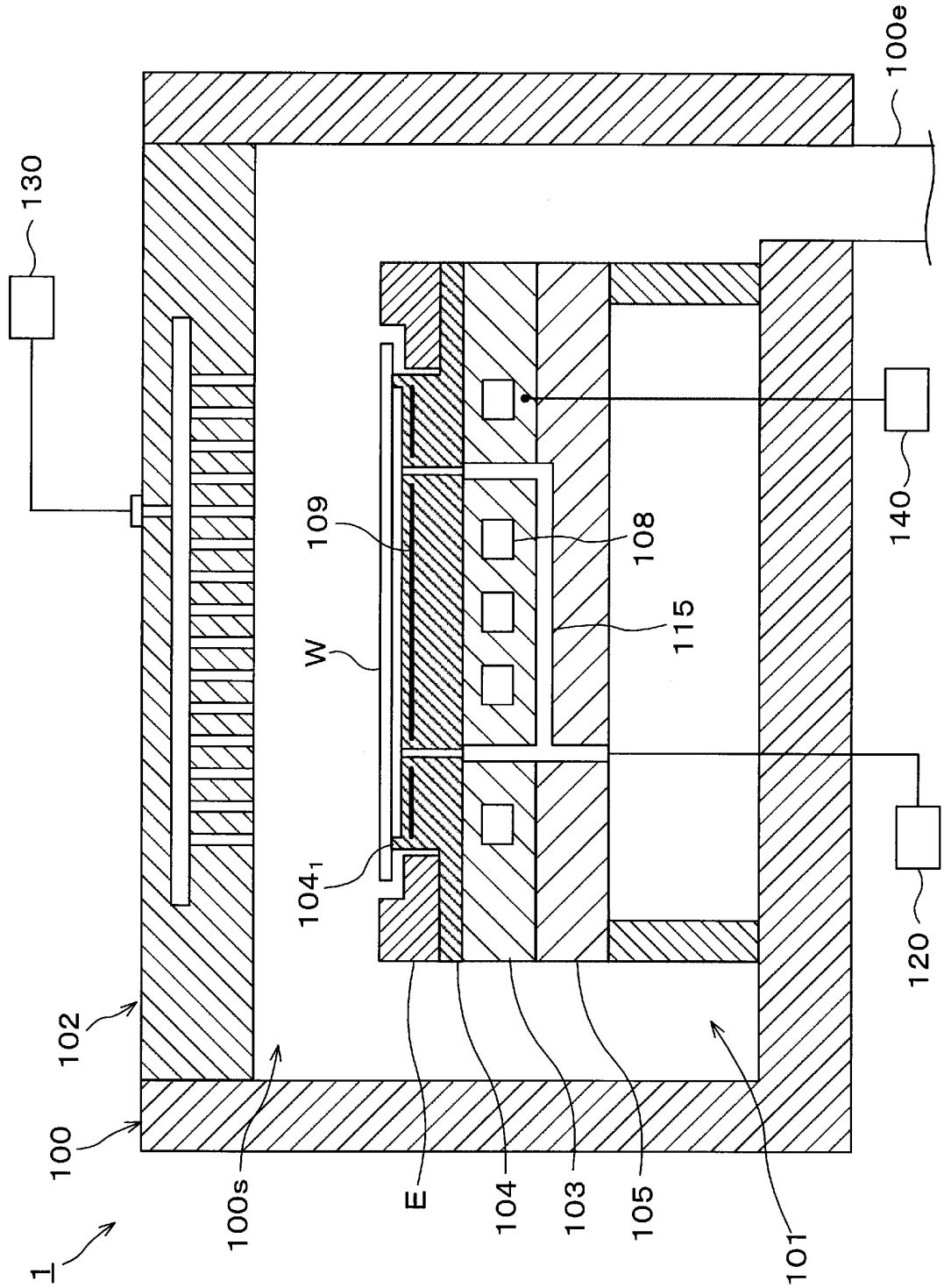
[図2]


130
131
132
160
170
171
172
173
100e
150
102a
102b
102c
102
100
114
D
109
W
113
104_1
E
104_2
108
115
122
121
120
100s
104
103
105
106
101
1

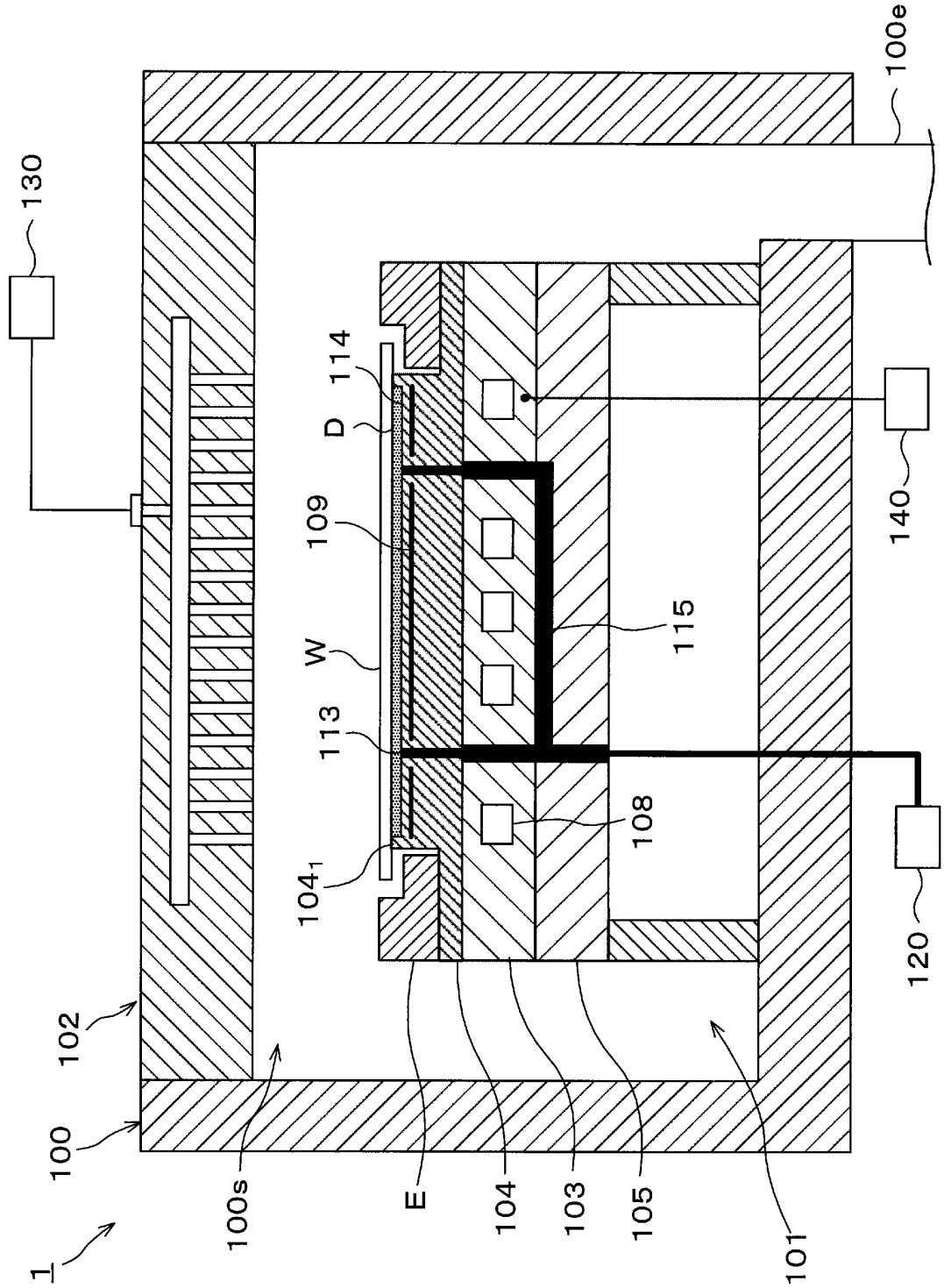
[図3]


START
S1
ウェハ載置
S2
伝熱媒体の供給により
伝熱層を形成
S3
プラズマ処理
S4
ウェハ離隔及び
伝熱層除去
S5
ウェハ搬出
END

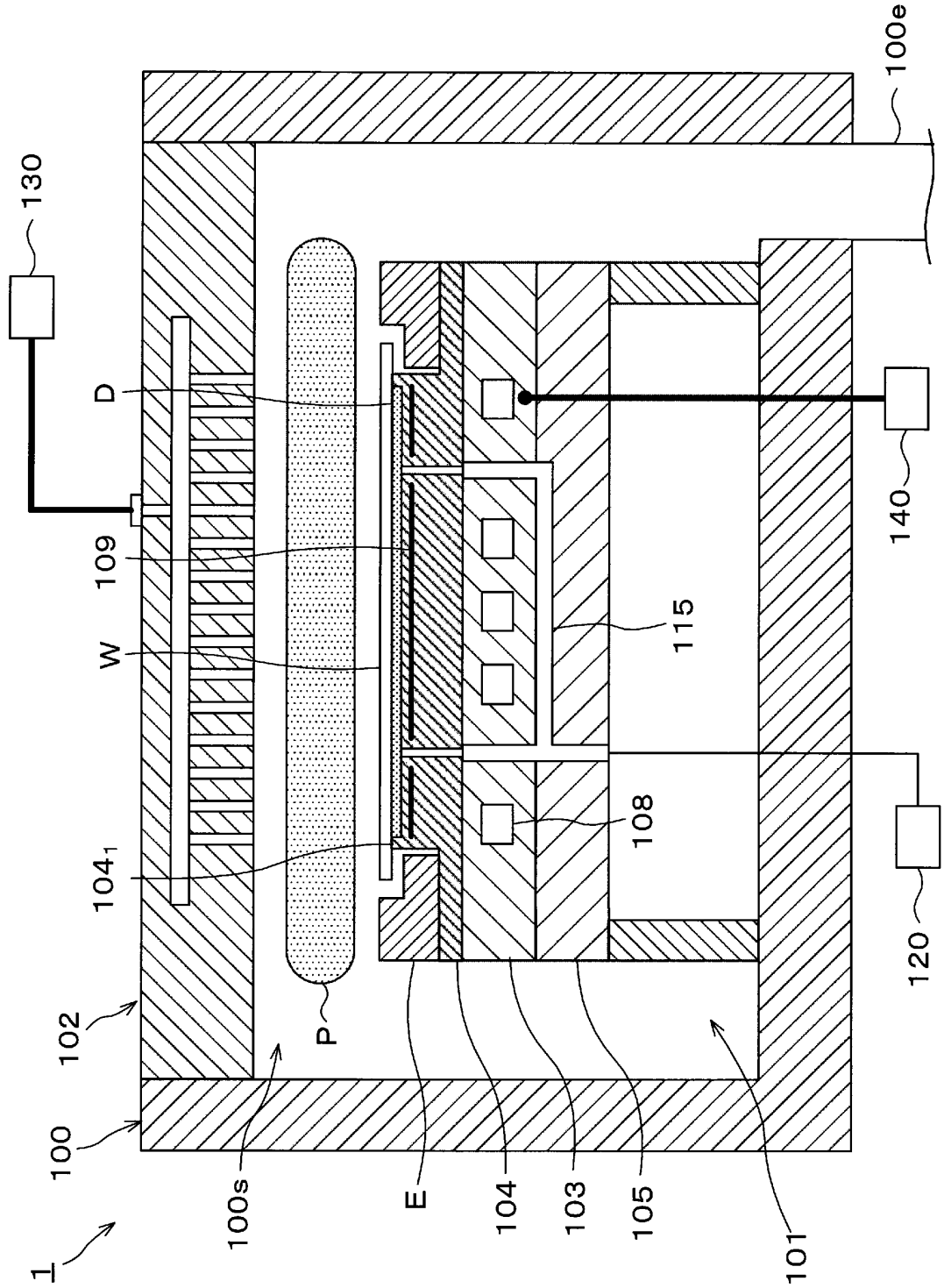
[図4]


100e
130
140
109
108
115
W
104_1
120
102
100
100s
E
104
103
105
101
1

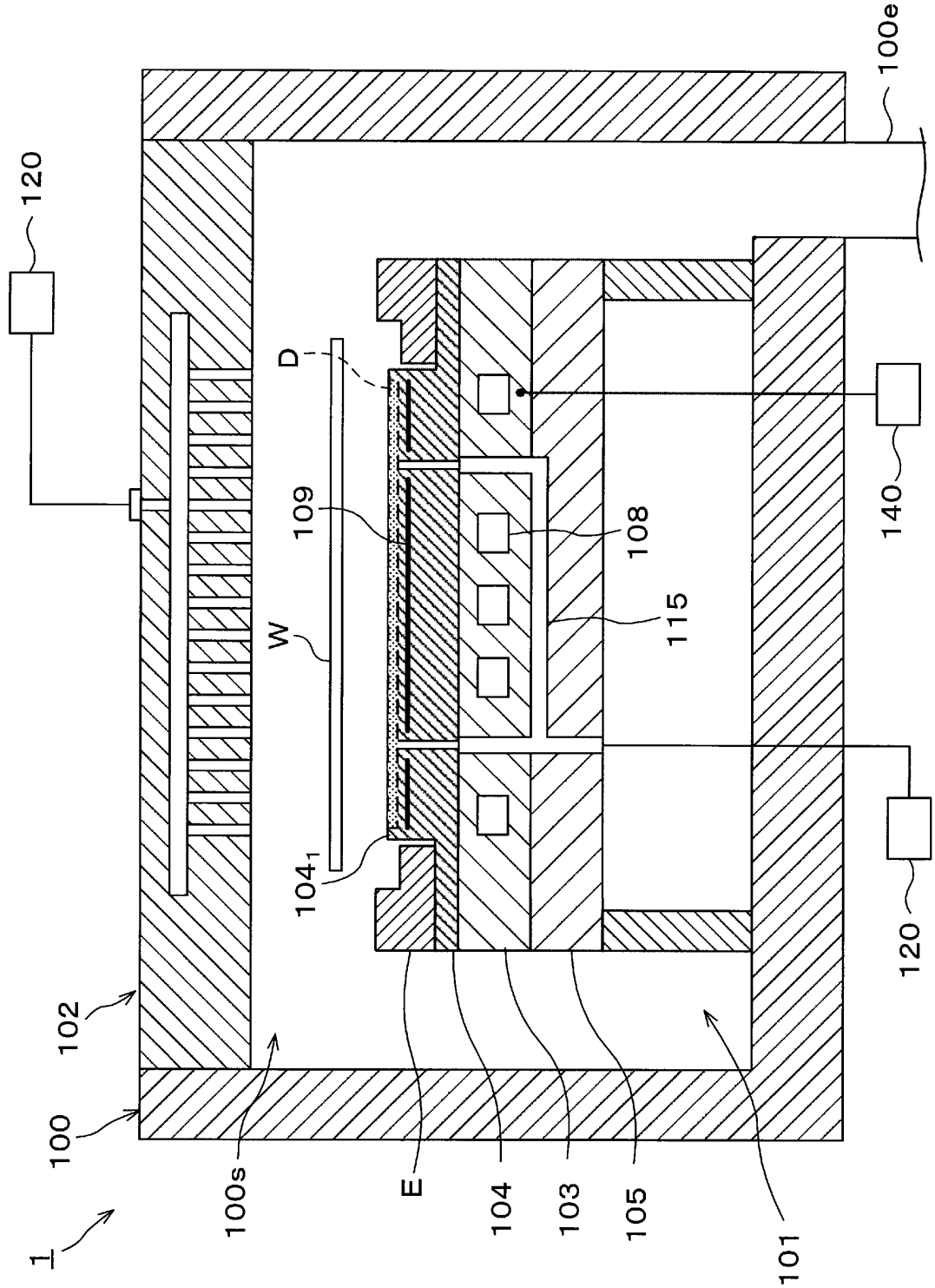
[図5]


100e
130
114
D
109
W
113
115
140
108
104_1
120
102
100
100s
E
104
103
105
101
1

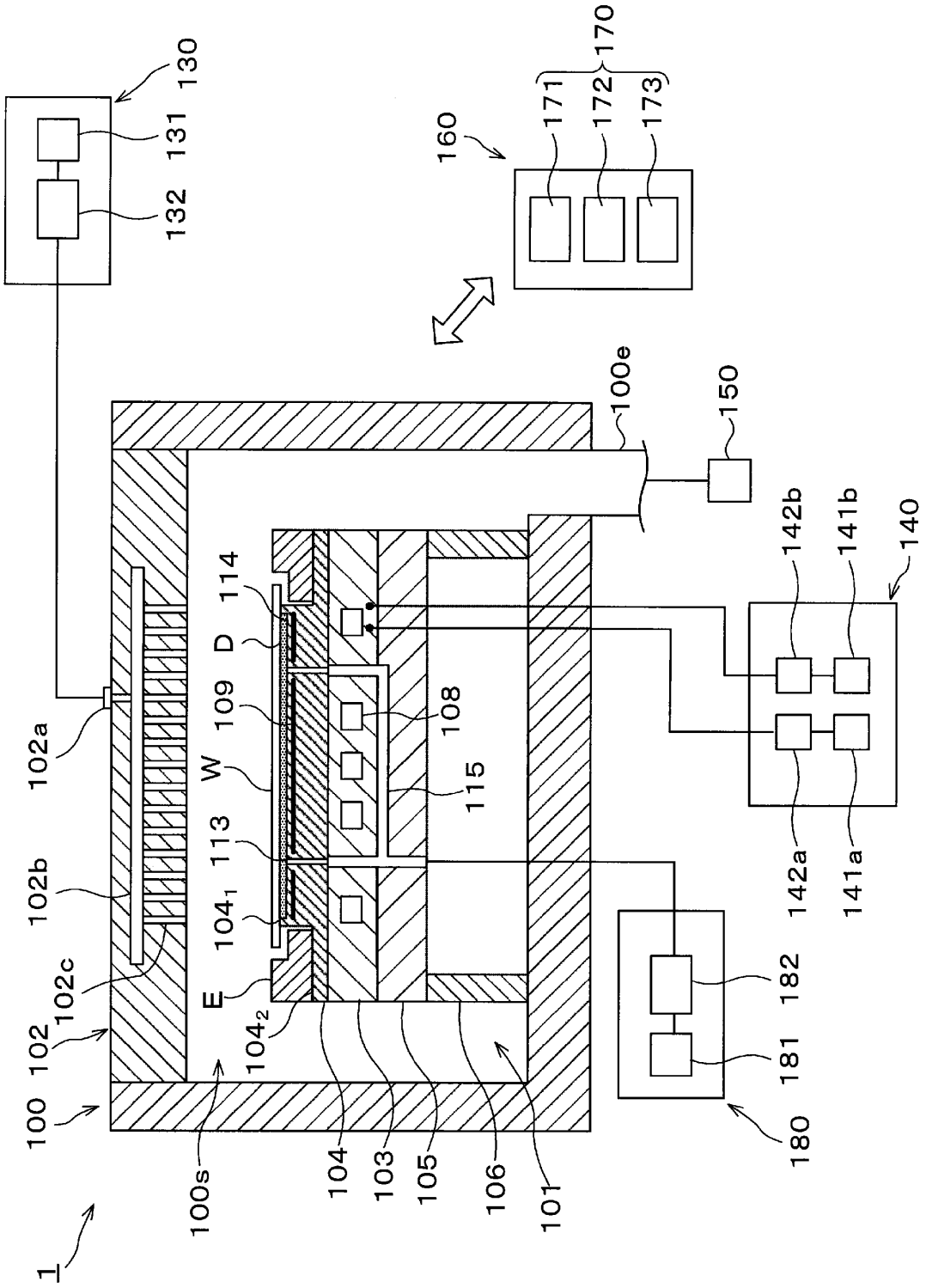
[図6]


100e
130
D
109
W
104_1
102
100
1
100s
P
E
104
103
105
101
115
108
140
120

[図7]


100e
120
D
109
W
104_1
108
115
140
120
102
100
100s
E
104
103
105
101
1

[図8]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170
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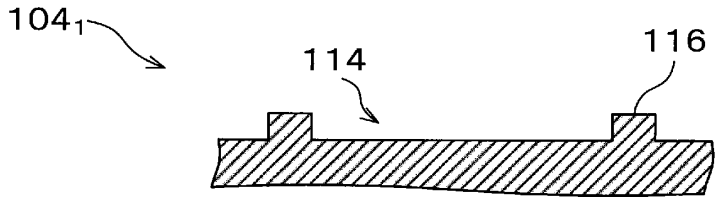
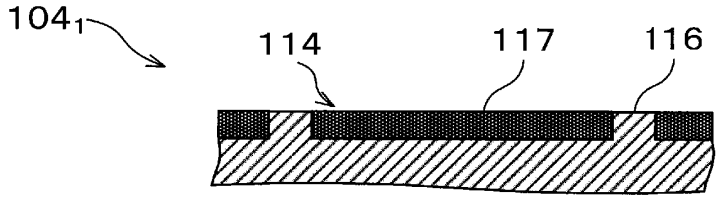
173
100e
150
140
142b
141b
114
D
109
108
102a
W
115
113
102b
104_1
102c
E
104_2
102
100
142a
141a
182
181
180
100s
104
103
105
106
101
1

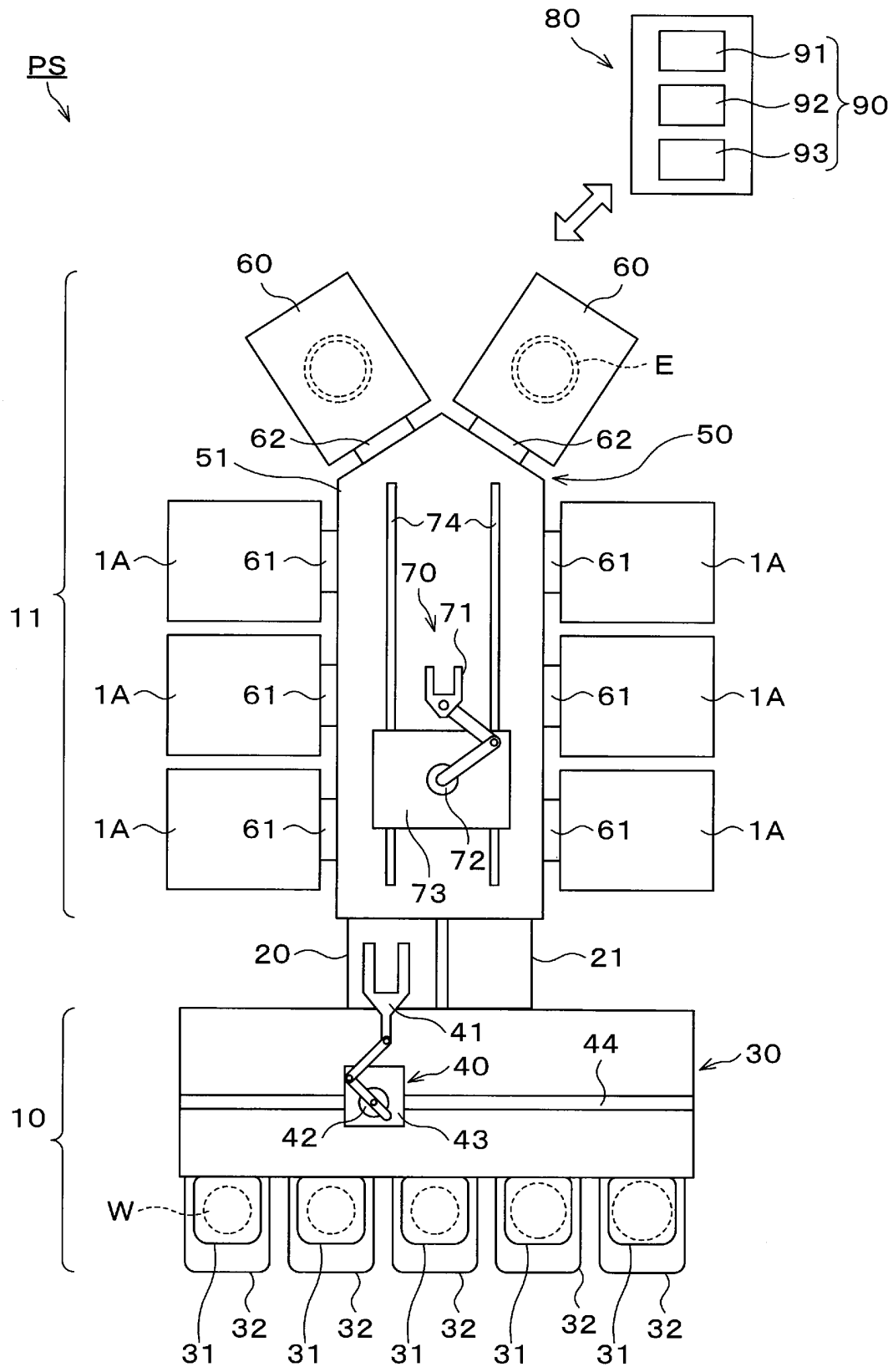
[図9]



[図10]



[図11]


PS
80
91
92
93
90
60
60
E
62
62
50
51
74
1A
61
70
71
61
1A
11
1A
61
61
1A
1A
61
61
1A
72
73
20
21
41
44
30
40
10
42
43
W
31
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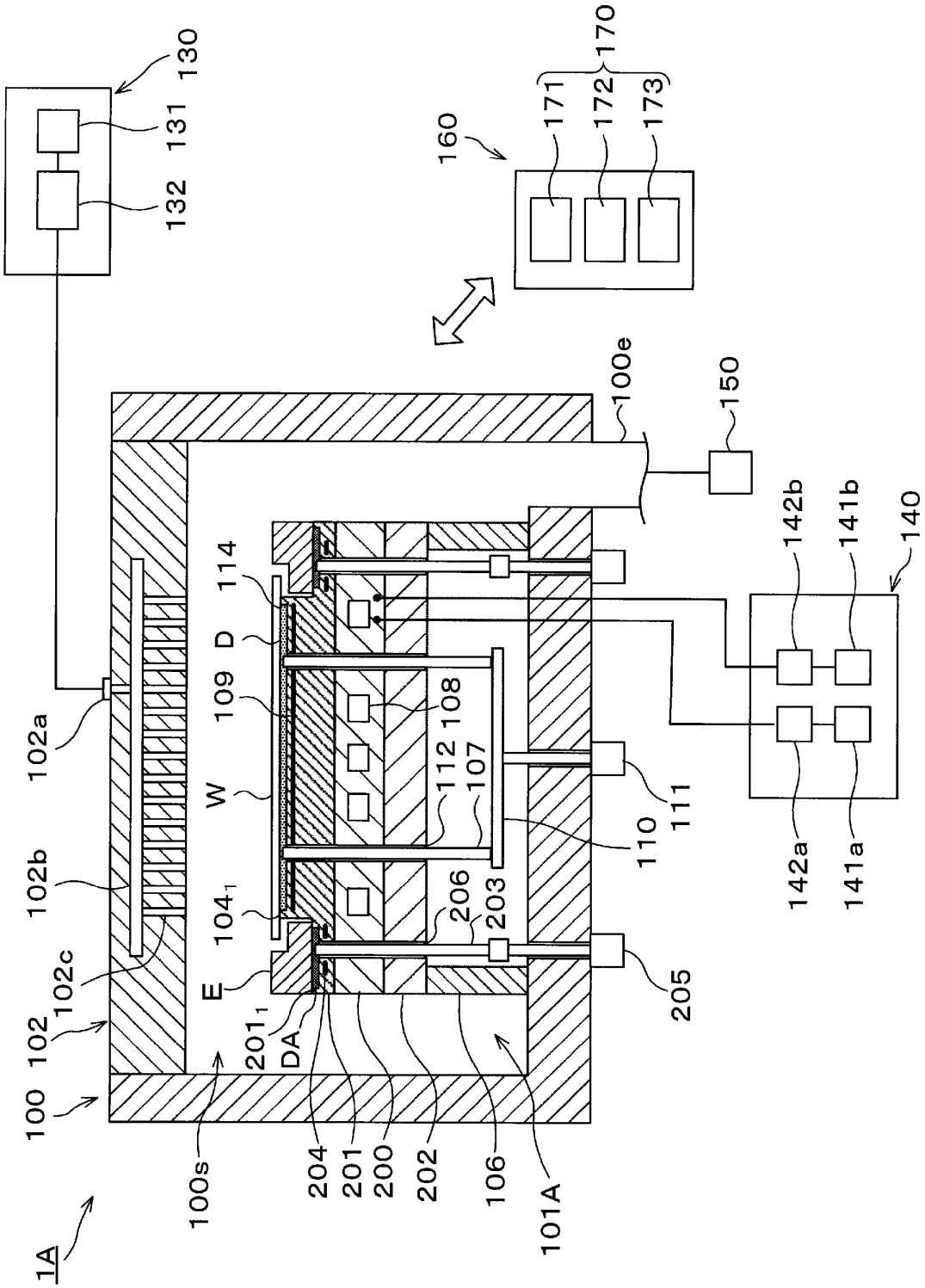
31
32

[図12]


130
131
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171
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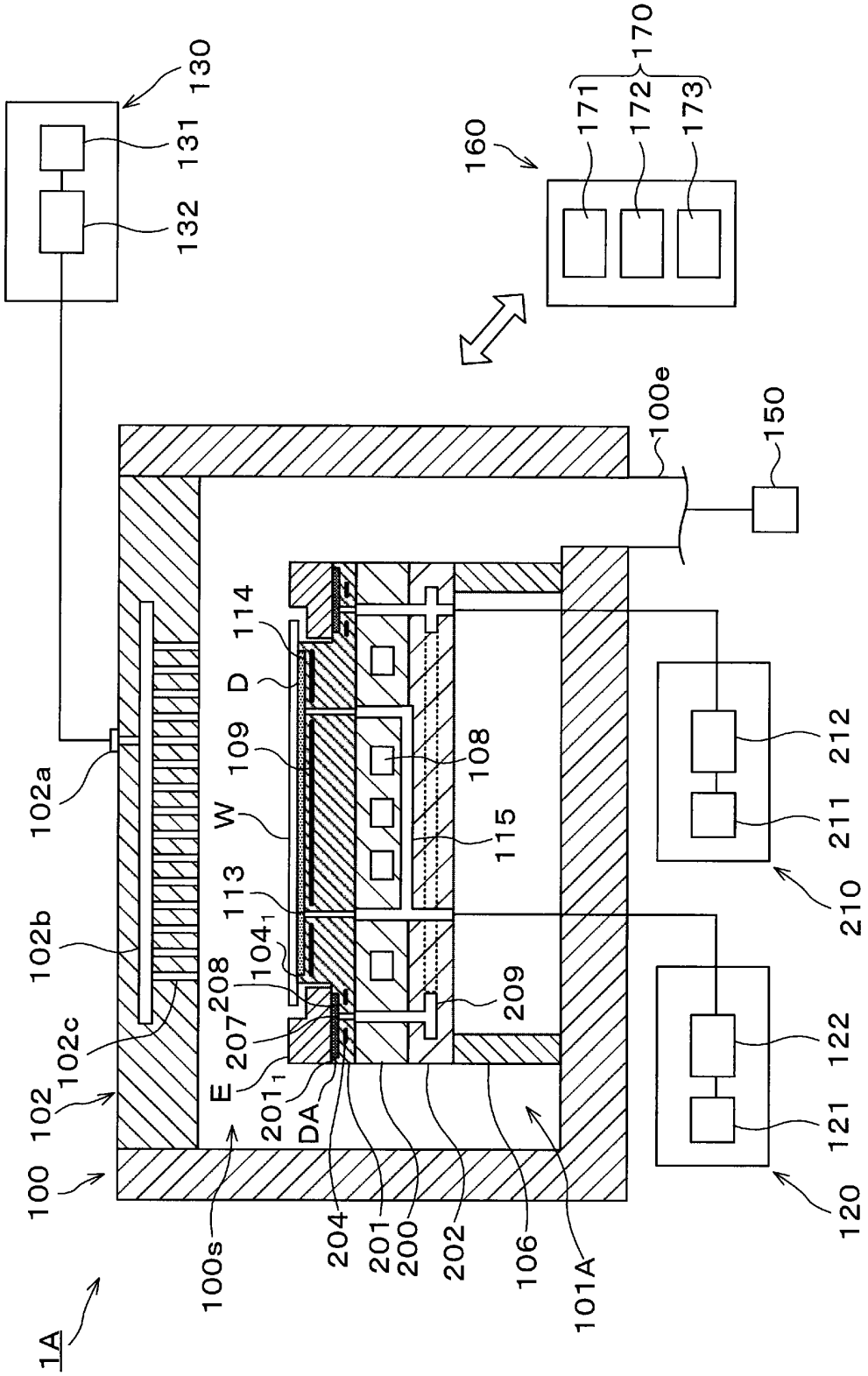
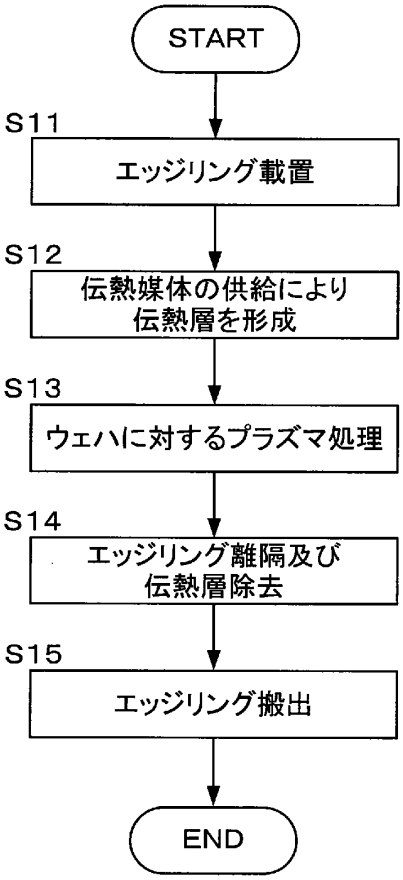
173
100e
150
140
142b
141b
142a
141a
114
D
109
108
112
107
W
110
111
102a
102b
102c
102
100
104_1
206
203
205
E
201_1
DA
204
201
200
202
106
101A
100s
1A

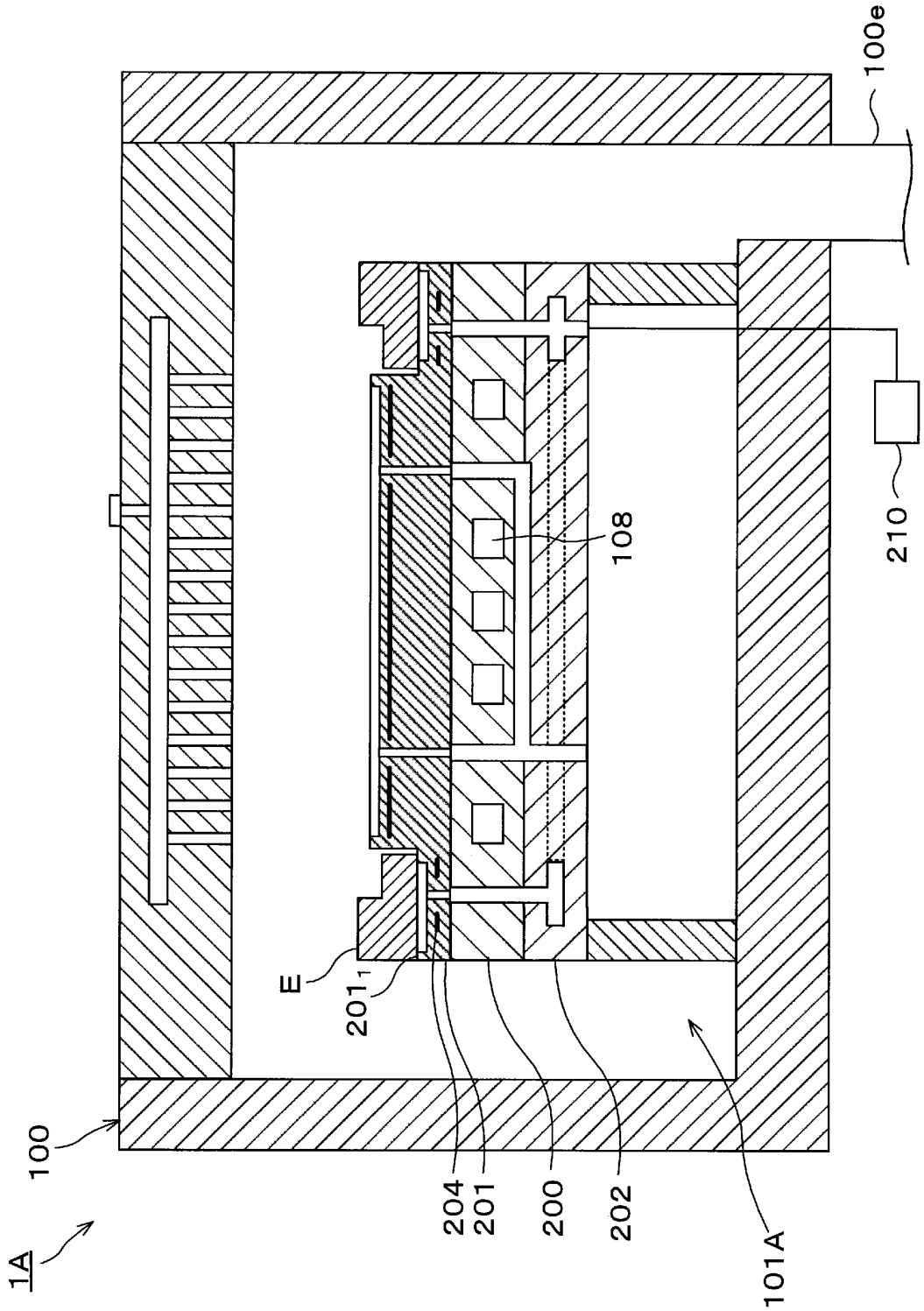
[図13]


130
131
132
160
170
171
172
173
100e
150
114
D
109
W
108
115
113
104₁
208
207
209
E
201₁
DA
102a
102b
102c
102
100
100s
204
201
200
202
106
101A
1A
212
211
210
122
121
120

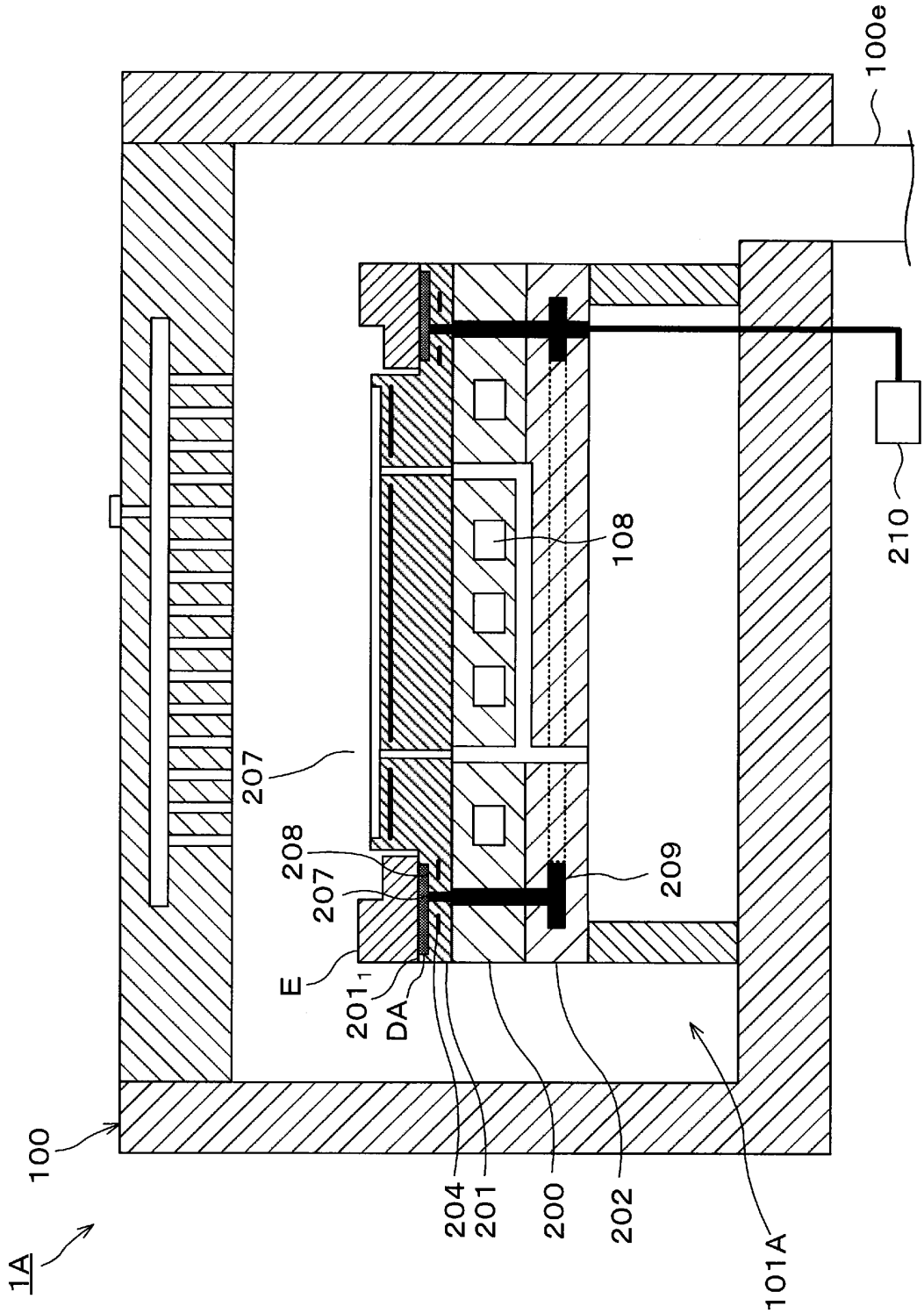
[図14]


START
S11
エッジリング載置
S12
伝熱媒体の供給により
伝熱層を形成
S13
ウェハに対するプラズマ処理
S14
エッジリング離隔及び
伝熱層除去
S15
エッジリング搬出
END

[図15]



[図16]



[図17]

